



PATENT APPLICATION

In re Application of:

Examiner: D. Esplin

Group Art Unit: 2851

October 31, 2002

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TECHNOLOGY CENTER, INC.

AMENDMENT

In response to the Official Action dated July 31, 2002, please amend the above-identified application as follows:

Please cancel the current abstract and insert the following. A marked-up copy showing the changes made to the abstract is attached hereto in Appendix A.

-- A scanning exposure apparatus for transferring a pattern of a master onto each of a plurality of shot regions defined on a substrate, while synchronously scanning the master and the substrate. The apparatus includes a master stage for moving the master, a substrate stage for moving the substrate, and a controller for controlling movement of the substrate stage during scanning exposure of the plurality of shot regions so as to assure that a setting distance in which